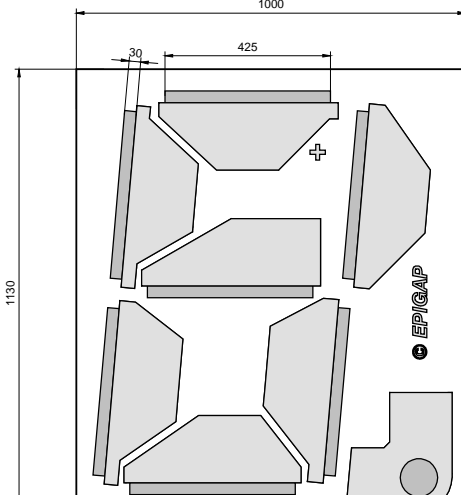


Radiation	Type	Technology	Electrodes
Red	Diffusion type	GaAsP/GaAs	P (anode) up

	typ. dimensions (µm)	
	<u>typ. thickness</u> 330 µm <u>cathode</u> Au-alloy metalization <u>anode</u> Al metalization	Application This miniature device is an excellent choice for applications where small size and reduced space are important factors such as complex displays in optical devices for laboratory, measurement, control- and medical equipment.

Miscellaneous Parameters

T_{amb} = 25°C, unless otherwise specified

Parameter	Test conditions	Symbol	Value	Unit
Temperature coefficient of λ_c	T _a = -40..120°C	T _C (λ_c)	0.15	nm/K
Operating temperature range		T _{amb}	-30 to +100	°C
Storage temperature range		T _{stg}	-40 to +125	°C

Optical and Electrical Characteristics

T_{amb} = 25°C, unless otherwise specified

Parameter	Test conditions ¹	Symbol	Min	Typ	Max	Unit
Forward voltage	I _F = 5 mA	V _F		1.7	1.9	V
Forward voltage	I _F = 20 mA	V _F		1.8	2.1	V
Reverse voltage	I _R = 100 µA	V _R	5			V
Luminous intensity/segment ²	I _F = 5 mA	I _v	60	85		µcd
Luminous intensity/segment ²	I _F = 20 mA	I _v	280	400		µcd
Luminous intensity/segment ³	I _F = 20 mA	I _v		710		µcd
I _v ratio segment to segment ²	I _F = 20 mA				1.75	
I _v ratio to adjacent chip	I _F = 20 mA				2.00	
Peak wavelength	I _F = 20 mA	λ_p	650	660	670	nm
Spectral bandwidth at 50%	I _F = 20 mA	$\Delta\lambda_{0.5}$		17		nm

¹Current for one segment

²Measured on bare chip on TO-18 header

³Measured on epoxy covered chip on TO-18 header

Labeling

Type	Lot N°	I _v (typ) [µcd]	V _F (typ) [V]	Quantity
EDC-660-19-01				

Packing: Chips in wafer pack or on adhesive film with wire-bond side on top

*Note: All measurements carried out with **EPIGAP** equipment